Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S1	1	MOS and (sidewall with (SiC or SiCN)) and BTBAS	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/05/31 09:14
S2	14	MOS and (sidewall with (SiC or SiCN))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/05/31 09:19
S3	7	MOS and ((carbon near containing) with (spacer or spacers))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/05/31 09:17
S4	2393	((438/216) or (438/287) or (438/303)).CCLS.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/05/31 09:19
S5	202	S4 and carbon	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/05/31 09:28
S6	15	SiCN same insulator	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/05/31 09:32
S7	93	carbon near (implant$3 or dop$3) same (sidewall or sidewalls)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/05/31 09:34
S8	65	carbon near (implant$3 or dop$3) same (spacers or spacer)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/05/31 09:42
S9	0	spacers with (ethylane and hexachlorsilane)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/05/31 09:42

S10	0	(ethylane and hexachlorsilane)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/05/31 09:42
S11	0	(ethylene and hexachlorsilane)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/05/31 09:42
S12	9	ethylene and hexachlorosilane	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/05/31 09:43